METHODS FOR CLEANING SUBSTRATES

ABSTRACT

A method for removing sand particles from a substrate is described. The method includes the step of treating the substrate with an acid solution comprising H_xAF_6, wherein A is selected from the group consisting of Si, Ge, Ti, Zr, Al, and Ga; and wherein H_xAF_6 is present at a concentration in the range from about 5 weight percent to about 40 weight percent.

Figure 2